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Interconnect-Centric Array Architectures for Minimum SRAM Access Time

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Abstract[‡]

Physical and generic models that analytically couple the array architecture of CMOS SRAMs with the wire lengths and fan-outs along critical paths to decode and sense data are reported. Verified to be accurate with published SRAMs, these models enable the design of optimal array architectures to minimize total access time by balancing communication distance limited wire delays with fan-out and area limited gate delays.

1. Introduction

CMOS SRAM circuit design paradigms that have been in practice for over two decades have taken advantage of improvements in circuit performance obtainable by scaling transistor dimensions [1,2]. While device performance improves with scaling, the distributed RC time constant per unit length of interconnections increases as the square of the scaling factor for minimum feature size [3]. Embedded SRAM cache sizes increase by approximately 2X every generation (Figure 1) to compensate for the increasing performance disparity between processor and main memory, the growing performance cost of off-chip accesses and as demands on its size increase with more sophisticated operating systems and applications [4,5]. The increasing severity of interconnect delays, reverse scaling of metal and insulator dimensions notwithstanding [6], in tandem with larger cache sizes directly translate into longer effective communication distances [7,8,9] across SRAM cache arrays mandating an interconnect-centric methodology for the design of large, high performance cache SRAMs.

Analytical models for SRAM access time previously developed in [10] and extended in [11] were applied to explore the impact of various SRAM cache organizations on its performance. More recently, the models in [10] combined with energy and area models were extended in [8] to project limitations on speed and power scaling of SRAMs. While the critical path descriptions in [10,11] apply well to small cache's used at the time [10] was published, they becomes increasingly incapable of addressing the complexities of two dimensional hierarchical array division, seen more recently in [12,13,14], as SRAM cache array densities evolve along the trends observed in Figure 1.

2. Hierarchical Array Division

Partitioning of an undivided array (Fig 2) into global vertical blocks (Fig. 3) results in shorter Word Lines (WLs). Shorter WLs translate into a smaller WL RC delay [15] but increase the wire lengths driven by stages preceding the WL driver. Further division and subdivision of the array into sub-global and sub-sub-global blocks, referred to as 'hierarchical word line division' in [16], was demonstrated to improve the WL decode delay in subsequent implementations [17] by limiting the increases in wire-lengths and total capacitance along the decode network. Increasing the number of hierarchical divisions beyond

a certain point, however, increases the fan-out of decode stages as well as the total area consumed by them [15]. Larger fan-outs and area constraints on the maximum W/L ratios of decode stages imposed by array efficiency requirements, directly translate into an increasing gate delay penalty to decode a WL. Balancing decreasing RC delays due to shorter wire-lengths with increasing gate delays due to larger fan-outs and area limited W/L ratios yields an optimal hierarchical division of the WL for a prescribed area constraint.

Hierarchically dividing the Bit Line (BL) into shorter local BL permits the same differential voltage across a local BL pair to develop sooner due to a smaller local BL capacitance seen by the cell [18]. Improvements in local BL delay obtained from reductions in BL length are limited by increases in the area consumed by local sense amplifiers and the delay of the global BL.

A rigorous analytical model that captures the fan-out, wirelength and area dependence of the decode network and the bit path on the architecture of the hierarchical array division would enable us to quantify the trade-offs and precisely identify optimal array configurations.

3. A Generic Critical Path Model

3.1. Array Architecture

The SRAM array of size M bits is assumed to be divided into identically sized nm 'macros' (Figure 4) where each macro can be considered an independent RAM [8]. Each macro stores part of the accessed word or a 'subword' with all macros activated simultaneously to yield the entire accessed word, n_{IO} bits wide. Each macro is assumed to be divided into \mathbf{n}_1 global subarrays given by (1a) in the Appendix, where n_{1x} equals the number of rows of global subarrays and \mathbf{n}_{1y} equals the number of columns of global subarrays as seen in Figure 4. Each global subarray may be further divided into n_2 subglobal subarrays in (1b). Similarly, further division of the subglobal subarray or subarrays further down the hierarchy are modeled in (1c), where the subscript, i, indicates the index of the hierarchical division. The smallest building block of this hierarchical division of the macro - the local subarray, is referred to as a block and has a width equal to the length of a word line, Ne cells wide and a height of N_r cells - equal to the length of a local bit-line, N_{BL} cells tall, times the number of BL divisions per block, d_{BL} (2). The total number of blocks in a macro is given by (3). The size, in bits, of each macro is given by (4). The WL decode network selects one of N_{WL} word lines given by (5a). The column decode network selects one of n_{BL} BL pairs given by (5b).

3.2. Decode Critical Path

The CMOS critical path circuit architecture to decode a WL may be completely defined with six parameters: (i) Choice of logic gates in each decode stage (ii) Logic depth (iii) Fan-in of each decode stage (iv) Fan-out of each decode stage (v) Geometries and resistivity of wires driven by each decode stage and (vi) Device widths of N and P channel devices in each gate along the decode path.

<u>Choice of logic gates:</u> Most CMOS SRAMs that implement the decode network with static CMOS use a decode stage

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comprising of a static CMOS NAND gate followed by an inverter [9]. Alternatives to static CMOS such as clocked decoding are commonly used as well. We assume static CMOS gates in this analysis for simplicity.

<u>Logic Depth</u>: The logic depth, n_{cp} along any path of the decode network (6) is given by both - the number of WLs to be decoded, N_{WL} as well as the average fan-in, $\overline{f_{in}}$ rounded to the nearest integer, of the NAND gates along that decode path. Two additional gates are added to account for the double inverter in the address input buffer. The number of address bits required to decode one of N_{WL} word lines is given by (7), where N_Z is the number of address bits required to decode one of N_r rows in each block. The number of decode stages along an $N_{bits} - N_{WL}$ decode network is given by (8).

Fan-in: A fan-in of two minimizes the delay of the decode network [8,9] (Figure 5) because every additional fan-in for a decode stage not only increases the delay of the NAND gate, but also doubles it's fan-out, increasing the total capacitance encountered along any single path while lowering the number of possible decode paths. Thus, every NAND gate between predecoder and word line is assumed to have a fan-in of two in this analysis.

<u>Fan-out & wire-length</u>: The fan-outs of each decode stage and also the maximum wire-lengths driven by each stage are determined by modeling the number of times a decode stage is replicated horizontally and vertically across the entire macro as a function of how the macro is divided hierarchically in two dimensions. The replica counts of each decode stage are modeled by imposing as boundary conditions, the replica counts of the address input buffers or the replica count of the WL. The replica counts of stage k, ^knrep with the stage identified by the left superscript, equals the product of its vertical replica count, ^knrep,

and its horizontal replica count, ${}^{k}nrep_{k}$ (9). In Figure 7 (inverters following the NAND gates are not shown for simplicity), for example, gate A drives a word line and has a replica count of 32. which is a product of a vertical replica count of 8 and a horizontal replica count of 4. The vertical or horizontal replica counts of each stage is equal to the product of the vertical or horizontal replica counts of the decode stages that drive each of it's inputs (10). Replica counts and their horizontal and vertical components of all gates in the example decode network of Figure 7 are listed in Table I. An address input buffer has a replica count of two since an address and its complement must both be available for a decoder. The address input buffers for address bits that decode one of several horizontal selections such as: Nr, n1x, n2x etc., are thus assumed to replicate twice vertically (11a). Similarly, the replica counts of the address input buffers for address bits that decode one of several vertical selections such as: n1y, n2y etc. are assumed to replicate horizontally twice (11b). The fan-out of a decode stage is calculated as the ratio of the replica count of the driven stage to the replica count of the stage whose fan-out is desired (12). The fan-outs of the stages in Fig. 7 are listed in Table I. The maximum horizontal or vertical wire-length between two decode stages along any decode path equals the difference in horizontal or vertical pitch (14) of the two decode stages (Figure 6). Since wire networks assume a Manhattan layout, the maximum interconnect length between two decode stages is given by the sum of the maximum horizontal and vertical wirelengths between these stages. (Wire-lengths of Fig. 7 are listed in Table I in units of cell dimensions, m_h, m_w. This calculation assumes a WL length of 128 cells).

<u>Device widths:</u> The loads driven along the WL decode network are given by (15)-(16) with gate beta ratios and expressions for delay given by (19). Optimal device widths that minimize total delay along the decode path depend on the gate used and the parasitic wiring being driven by each gate [9]. The optimal device width is calculated using (20)-(21). Device and Interconnect process parameters assumed in the examples are listed in Table 2.

The model for replica count of each decode stage, the W/L ratio for the NFET devices and the beta ratio of each gate permits us to estimate the area of a stage along all decode paths using an empirical model from [8] given in (22). Although (22) was developed in [8] for WL drivers, it could apply reasonably well to other decode stages since they too, like the WL driver comprise of a 2-input NAND gate followed by an inverter. The total area consumed by decode stages along any decode path is given by (28).

3.3. BL Architecture and delay path model

The local bitline delay is modeled, as in [9] in (23), where ΔV equals the sensitivity of the local sense amplifier, typically 200mV or less [9] and I_{read} equals the read current that flows through the two series connected NFETs in the memory cell. The local BL capacitance, the total capacitance at the output of the multiplexer that drives the input to the local sense amplifier, and the capacitance seen at the input to the local sense amplifier is modeled in (24-26). The local sense amplifier drives its output across the height of the macro along a global BL with a delay given by (27a). The total BL delay is given by the sum of (23) and (27b). This sum captures the dependence of BL delay on the architecture of the horizontal division of the block and the macro.

4. Optimal Array Division

The critical path models for decode and sense operations are verified with published SRAM arrays in Table 4. The device/interconnect parameters reported in these publications are listed in Table 2 and their array architectures in Table 3 (Figures 8-11). The WL RC response time improves with smaller N_c due to a shorter WL length. The BL response time improves with smaller N_r due to a smaller BL capacitance. Shrinking N_c lowers power dissipation as well since a smaller N_c directly translates into fewer cells dissipating read current during an access. Lowering Nr also improves power dissipation since a smaller BL capacitance requires less recovery power after a write operation. Thus, lowering Nc and Nr yields substantial improvements in the energy consumed by a data read operation. The array architecture defined by its hierarchical division in two dimensions into \mathbf{n}_{B} blocks (3) primarily determines the overheads in gate and interconnect delays that accompany reductions in N_c and N_r . Determining each of the horizontal and vertical hierarchical components of n_B so that the sum of the gate and interconnect delay components are at a minimum leads to an optimal array architecture. Figs. 8c,9c & 11 plot the dependencies of decode and sense delay as N_c and N_r are decreased.

5. Summary and Conclusions

New, physical and generic models for SRAM access time are reported. These couple the hierarchical architecture of the array with the definition of the decode and sense critical paths. Delays predicted by these models were verified with published data. Optimal array architectures that minimize the decode and sense delays by balancing decreasing interconnect delays with increasing fan-out and area limited gate delays are calculated using the proposed models.

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 Table 1: Replica counts, fan-outs and maximum wire-lengths in units

 of cell dimensions driven by decode stages for example in Figure 8

Gate	nrep	nrep _v	nrep _h	fout	L max	$L \max_{v}$	L max _h
Α	32	8	4	1	128	0	128
В	8	8	1	4	384	0	384
С	4	1	4	8	7	7	0
Z	2	1	2	2	128	0	128
X	2	2	1	4	3	3	0

 Table 2: Please see next page

Table 4: Comparison of references with new model

	[15]	New	[16]	New	[13]	New
		model		model		model
t _{WL}	-	9.5ns	7.8ns	8.6ns	.95ns	1.1ns
t _{BL}	-	2.1ns	2.0ns	2.3ns	-	.16ns
n_{1y}	8	4	4	4	8	8
n_{1x}	1	(1)	1	(1)	1	(1)
n_{2y}	1	(1)	8	8	1	(1)
<i>n</i> _{2<i>x</i>}	1	(1)	1	(1)	8	8
N _c	32	32	128	128	256	256
N _r	256	(256)	1024	(1024)	256	256

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 Table 3: Array Architecture parameters for Examples in Figures 9-11

Symbol	Parameters as listed in the			
	References			
	1	2	3	
	[15]	[16]	[13]	
М	64Kb	4Mb	18Mb	
n _{IO}	8b	4b, 1b	72b	
$nm_x \times nm_y$	1x1	1x1	2x2	
$n_{1x} \times n_{1y}$	1x8	1x4	1x8	
$n_{2x} \times n_{2y}$	1x1	1x8	8x1	
$n_{3x} \times n_{3y}$	1x1	1x1	1x1	
$n_{4x} \times n_{4y}$	1x1	1x1	1x1	
n _B	8	32	64	
d_{BL}	1	1	2	
N _r	256	1024	256	
N _c	32	128	256	
N _{WL}	2048	32768	16384	
N _{straps}	None	None	8	
m _w	21.0µm	3.5µm	2.22µm	
m _h	24.5µm	5.3µm	2.52µm	
WLL frac	1.0	1.0	0.5	

Symbol	Parameter	[15]	[16]	[13]
L, Leff	Channel length	2µm	0.6 µm	0.18, 0.14 µm
t _{ox}	Gate oxide thickness	400 A	150 A	30 A
V _{dd}	Supply voltage	5 V	3.3 V	1.5 V
V _{to}	Device threshold voltage	(1.0 V)	(0.8 V)	0.32 V
c _{go}	Min. geom device Gate oxide capacitance	(3.45 fF)	(0.828 fF)	(0.373 fF)
c _{do}	Min. geom device junction capacitance	(2.0 fF)	(0.51 fF)	(0.145fF)
Idsatn,0	Min. geom N device Drain sat. current	(290 µA/µm)	(505 µA/µm)	0.95mA/µm
I _{dsatp,0}	Min. geom. P device Drain sat. current	(104 µa/µm)	(278 µA/µm)	410μA/μm
V _{dsat}	Maximum NFETDrain saturation voltage	(1.93 V)	(1.15V)	(0.684V)
Na	NFET substrate doping concentration	$(2.98 \times 10^{16} \text{ cm}^{-3})$	$(1.466 \text{x} 10^{17} \text{ cm}^{-3})$	$(3.8 \times 10^{17} \text{ cm}^{-3})$
ρ_{WL}, ρ_n	Resistivity of metal level n	Poly, Salicide	Salicide, Al	Salicide, Al
ζn	Capacitance per unit length	2.1pF/cm		
T _n	Thickness of metal level n	(2µm)	(1.0µm)	250nm (poly WL)
				700nm (M3 BL, WL)
				1600nm (M5 GBL,
				GWL)
Λ_n	Aspect ratio of metal level n	1	2	(1) poly WL
				2.2 (M3: WL.BL)

Table 2: Device & interconnect parameter inputs for Figures 9-11. Parameters in parenthesis are calculated/estimated

Appendix:

Appendix:
(a)
$$n_{1} = n_{x} \times n_{y}$$
; ((b) $n_{2} = n_{x} \times n_{y}$; ((c) $n_{1} = n_{u} \times n_{y}$; (2) $N_{v} = N_{uv} \times d_{ut}$; (3) $n_{1} = n_{v} \times N_{v} \times ... \times 1 = \prod_{i}^{i} n_{i}(4) \frac{M_{mm}}{mm} = n_{u} \times N_{v} \times N_{v}$;
(5a) $N_{uv} = n_{v} \times N_{v}$; (5b) $n_{BL} = \frac{N_{v} \times n_{B} \times mw}{n_{O}} d_{BL}$; (6) $n_{op} = 2 \times \log_{T_{u}} [\log_{2}] N_{uv}] + 2 = 2 \times \log_{T_{u}} [\log_{2}] [n_{u} \times N_{v}] + 2$
(7) $N_{uv} = \log_{2}[N_{uv}] = \log_{2}[n_{u} \times N_{v}] = \log_{2}[n_{u}] + \log_{2}[n_{v}] + \log_{2}[N_{v}] + N_{v}$; (8) $N_{uven} = \log_{T_{u}} [N_{uv}]$; (9) $^{h}nrep = ^{h}nrep_{v} \times ^{h}nrep_{v}$;
(10a) $^{h}nrep_{v} = n_{u} \times n_{2v} \times ... \times 1 \times N_{v}$; m_{v} nrep_u = $\prod_{v} \times n_{2v} \times n_{2v}$; (11a) $^{h}nrep_{v} = 2$; $^{h}nrep_{u} = 1(11b)^{h}nrep_{v} = 1$; $^{h}nrep_{v} = 2$; $^{h}nrep_{v}$; (14a) $^{h}L \max_{v} = n_{u} \times n_{2v} \times ... \times 1 \times N_{v} \times m_{u} \times \left(\frac{1}{inrep_{v}} - \frac{1}{inrep_{v}}\right)$; (14b) $^{h}L \max_{v} = n_{u} \times n_{2v} \times ... \times 1 \times N_{v} \times m_{u} \times \left(\frac{1}{inrep_{v}} - \frac{1}{inrep_{v}}\right)$; (14b) $^{h}L \max_{v} = n_{u} \times n_{2v} \times ... \times 1 \times N_{v} \times m_{u} \times \left(\frac{1}{inrep_{v}} - \frac{1}{inrep_{v}}\right)$; (15b) $^{HZ}\mathfrak{M}_{total} = \frac{^{HZ}n_{v} ^{HZ}R_{p} \times m_{w} \times N_{c}}{(^{HZ}n_{u} + ^{HZ}n_{p}) \times N_{strass}}$;
(16) $^{P}C_{total} = N_{v} \left(2c_{go} + m_{w} \times \left[^{HZ}v_{u} + ^{HZ}v_{p}\right]\right)$; (15b) $^{HZ}\mathfrak{M}_{v} = \frac{1}{c_{w}} \sqrt{\frac{qN_{u}v_{st}}{4q_{f}}}$; (19) $^{P}t_{pd} = \frac{^{P}C_{total} !^{Hd}}{p_{f_{u}} + N_{u} r_{s}} \times !^{HZ}n_{s} !^{HZ$







Figure 2,3: Undivided and divided arrays.

Figure 1: Historical trends in embedded SRAM cache density.



analytically coupling the wire lengths and fan-outs driven by each decode stage with the architecture of the array. Area consumed by decoders and area constraints on maximum W/L ratios for decoders may also be easily calculated using this model. Inverters following NAND gates are not shown for simplicity.

Figure 6: Maximum wire length between decode stages equals their difference in pitch



Figure 11a: Decode delay dependence on number of global subarrays, n_{1y} in Fig. 11 Figure 11b: Decode delay dependence on the number of subglobal subarrays n_{2x} in Fig. 11 Figure 11c (at right): Sense delay dependence on the number of subglobal subarrays n_{2x} in Fig. 10.



100

N_c=256

0e+00